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(54) CAPACITIVE ELEMENT AND METHOD FOR MANUFACTURING THE SAME

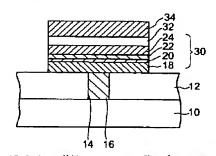
(57) Abstract:

PROBLEM TO BE SOLVED: To provide a capacitive element having a ferroelectric film capable of preventing oxidation of a plug in a process for crystallizing a capacitor dielectric film in a stacked capacitive element, and preventing diffusion of iridium to the capacitor dielectric film.

SOLUTION: This capacitive element is provided with a lower electrode 30 constituted by successively forming first conductive films 18 and 20 including first metal. a second conductive film 22 formed on the first conductive films 18 and 20, and made of metallic oxide including second metal different from the first metal, and a third conductive film 24 formed on the second conductive film 22, and made of third metal different from the first metal.

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本発明の第1実施形態による容量素子の構造を示す概略断面図



10 シリコン基板

12 層間絶縁膜

14 コンタクトホール

16 ブラグ

18 イリジウム膜

20 酸化イリジウム膜

22 酸化プラチナ膜

24 ブラチナ膜

30 下部電極

32 キャパシタ誘電体膜

34 上部管径